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Optical-field-induced electron emission in a dc-biased nanogap

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We construct an analytical formulation for nonlinear photoelectron emission in a dc-biased metallic nano-vacuum gap triggered by a laser field, by exactly solving the one-dimensional time-dependent Schrödinger equation. We theoretically investigate the photoelectron energy spectra and emission current from left- and right-side surfaces of the asymmetric nanojunction with various dc biases, laser fields and gap distances. The underlying photoemission mechanisms transitioning form multiphoton over-barrier emission to photon-assisted field tunneling, and the spatiotemporal dynamics of electron transport inside the gap are analyzed in detail. Our calculation shows applying a dc field could greatly reduce the interference oscillation in the transmission current in the nanogap, due to the shift of dominant emission away from multiphoton over-barrier regime. Our results demonstrate that, besides the dc bias, varying the gap spacing could strongly influence the rectification on the photoelectron emission in a dc-biased metal-vacuum-metal gap. Our study provides useful guideline to the design of ultrafast nanogap-based signal rectification devices, such as photoelectron emitters and photodetectors, by choosing optimal combination of dc bias, gap spacing, and material properties.

I. INTRODUCTION

Optical-field-induced electron emission from nanostructures enables the control of electron dynamics on ultrashort space and time scales [1-16], due to the nanoscopic confinement of optical electric field and the resulting large field enhancement factor on the nanosurface, which makes it crucial in many research areas, such as high-resolution electron microscopy [17–20], highly coherent electron sources [21–23], tabletop laser accelerators [24] and emerging nanoelectronic devices [25–29]. Recently, laser-driven photoelectron emission in the nanoscale two metallic tips has drawn substantial interests [30–38], due to its promising applications to surface-enhanced spectroscopies, nonlinear optics, nanophotonics, and ultrafast and highly sensitive photodetection at the room temperature. Rybka et al. [32] reported laser-induced sub-femtosecond photoelectron tunneling in a nanoscale metal-vacuum-metal gap. Higuchi et al. [31] explored the rectification effect of dc-biased two-metal-nanotip junction in ultrafast multiphoton photoemission. Piltan et al. [34] demonstrated the plasmon-enhanced photoemission in metal-vacuum nanotip array and optical tunability from geometric degree of freedom. Ludwig et al. [36] presented the strong dependence of dynamics of nanoscale electron transport between two metal tips on the temporal profile of driving laser pulses. Turchetti et al. [38] studied the impact of dc bias on photoemission from metal surfaces surrounding a nano-vacuum gap.

While there have been significant theoretical efforts to study intense-field nonlinear photoexcitation and tunneling emission process in solid systems [10,39–50], these theoretical models are valid only in certain emission regimes. For example, the perturbative theory [39, 40] typically uses strong field approximation, and the Floquet theory [45, 47] is developed without considering the effect of DC field. Generally, numerical solutions, like solving the time-dependent density function theory [30,36,37,51,52] and Schrödinger equation [38,53], are generally implemented to study the photoelectron emission in the nanogap, such as electron transfer in plasmonic nanotips [36], nanoparticle dimmers [51] and bowtie nanoantennas [53]. To reveal more clearly the underlying emission physics, most recently we developed an exact analytical model for the photoelectron emission in the metal-vacuum-metal nanogap [54], where the dependence of emission properties on the laser field, gap spacing, and metal material is studied. However, it only accounts for the symmetric nano-vacuum system in which the net photoemission current is physically unobservable (i.e., the time-averaged net photocurrent is zero). For asymmetric scenarios (e.g., operating under a dc bias [30,31,34,38]) that generates experimentally

observable net photocurrent, there is still a lack of an exact analytical theory (or theories) that can systematically characterize the parametric dependence of emission properties and distinctly reveal the interplay of various processes on which emission depends.

In this work, we construct an analytical model for nonlinear optical-field-triggered photoemission in a dc-biased asymmetric metal-vacuum-metal nanojunction, by exactly solving the time-dependent Schrödinger equation (TDSE). Our model is valid in various emission regimes spanning multiphoton absorption and emission, photon assisted tunneling, optical field emission and dc field emission. We analyze the photoelectron emission properties from both sides of the nano-vacuum gap with various combinations of dc fields, laser intensities and gap distances. Our results show that the external dc bias could greatly enhance the photoemission current and reduce the quantum mechanical interference oscillations in the transmission current. Furthermore, the change of the gap spacing is found to strongly influence the rectification on the photoelectron emission. This may offer practical guidance to improve signal efficiency of advanced ultrafast nanogap-based photoelectron emitters and photodetectors consisting of nanotips, nanobowties and nanoparticles, by the choice of proper combination of dc bias, gap distance, and material properties.

II. ANALYTICAL FORMULATION

The schematic of the configuration for a meta-vacuum-metal nanogap with a dc bias under the illumination of optical field is shown in Fig. 1(a). With the external applied dc voltage V, the symmetry of the metal-vacuum-metal system is broken. This means that under the same illumination condition, the left and right metal-vacuum interfaces of the nanogap in Fig. 1(a) have different photoemission properties. Therefore, we analytically model photoelectron emission from left- and right-side metal-vacuum interfaces, respectively. Here, the laser field $F_1 \cos(\omega t)$ is assumed to be perpendicular to the flat metal surfaces and cuts off abruptly at the surfaces, where F_1 is the amplitude of the laser field and ω is the angular frequency. For simplicity, the impact of image and space charges [29,55,56] is neglected in this work.

For photoemission from the left metal-vacuum interface of the gap in Fig. 1(a), electrons in the left metal with the initial energy ε would see a potential barrier subjected to a positive dc electric field $F_0 = V/d$ (> 0) and laser field $F_1 \cos(\omega t)$, as shown in Fig. 1(b). Thus, the time-dependent potential energy in the left metal (x < 0), vacuum gap (0 < x < d) and right metal ($x \ge d$) of Fig. 1(a) reads as [10,12,54,57–59],

$$\Phi(x,t) = \begin{cases} 0 & x < 0\\ E_F + W - eVx/d - eF_1xcos(\omega t) & 0 \le x < d\\ -eV - eF_1dcos(\omega t) & x \ge d, \end{cases}$$
(1)

where E_F and W are the Fermi energy and work function of the left metal respectively, e is the elementary charge, and V is the magnitude of the applied dc bias.

To obtain the electron emission probability, we solve the TDSE,

$$i\hbar \frac{\partial \psi(x,t)}{\partial t} = -\frac{\hbar^2}{2m_e} \frac{\partial^2 \psi(x,t)}{\partial x^2} + \Phi(x,t)\psi(x,t), \tag{2}$$

where \hbar is the reduced Planck constant, $\psi(x, t)$ is the electron wave function, m_e is the electron mass, and $\Phi(x, t)$ is the potential energy given in Eq. (1).

For x < 0, the electron wave function is,

$$\psi_1(x,t) = \exp\left(-\frac{i\varepsilon t}{\hbar} + ik_0 x\right) + \sum_{n=-\infty}^{\infty} R_{1n} \exp\left(-i\frac{\varepsilon + n\hbar\omega}{\hbar}t - ik_n x\right), x < 0$$
(3)

which denotes the superposition of an incident plane wave with initial energy ε and a set of reflected plane waves with reflection coefficient R_{1n} and energies $\varepsilon + n\hbar\omega$, where the wavenumber $k_0 = \sqrt{2m_e\varepsilon/\hbar^2}$ and $k_n = \sqrt{2m_e(\varepsilon + n\hbar\omega)/\hbar^2}$.

For $0 \le x < d$ in the gap, the exact solution to Eq. (2) is found to be (see Appendix A for the method),

$$\psi_{2}(x,t) = \sum_{n=-\infty}^{\infty} \exp\left[-i\frac{\varepsilon + n\hbar\omega}{\hbar}t\right] \exp\left[-\frac{ie^{2}VF_{1}\sin(\omega t)}{\hbar dm_{e}\omega^{3}} + \frac{ixeF_{1}\sin(\omega t)}{\hbar\omega} + \frac{ie^{2}F_{1}^{2}\sin(2\omega t)}{8m_{e}\hbar\omega^{3}}\right] \times [T_{1n}Ai(-\eta_{n}) + T_{2n}Bi(-\eta_{n})];, \quad 0 \le x < d$$
(4)

which represents the superposition of a set of transmitted and reflected electron waves inside the gap, where $\eta_n = \left[\frac{E_n}{eV}d + x + \frac{eF_1\cos(\omega t)}{m_e\omega^2}\right] \left(\frac{2em_eV}{\hbar^2 d}\right)^{\frac{1}{3}}$, the drift kinetic energy $E_n = \varepsilon + n\hbar\omega - E_F - W - U_p$, the ponderomotive energy $U_p = e^2 F_1^2 / 4m_e\omega^2$, *Ai* and *Bi* are the Airy functions of the first and second kind respectively, and T_{1n} and T_{2n} are the coefficients.

For $x \ge d$, an exact solution of electron wave function is,

$$\psi_{3}(x,t) = \sum_{n=-\infty}^{\infty} T_{3n} \exp\left(-i\frac{\varepsilon + n\hbar\omega}{\hbar}t\right) \exp\left[ik_{n}x + i\frac{eF_{1}d\sin(\omega t)}{\hbar\omega}\right], x \ge d \qquad (5)$$

which shows the superposition of electron plane waves transmitted into the right metal in Fig. 1(a) with energies $\varepsilon + n\hbar\omega$, due to multiphoton absorption (*n*>0), direct tunneling (*n*=0) and multiphoton emission (*n*<0) [10,50], where the wavenumber $k_n = \sqrt{2m_e(\varepsilon + n\hbar\omega + eV)/\hbar^2}$ and T_{3n} is the transmission coefficient.

The coefficients T_{1n} , T_{2n} , and T_{3n} (and therefore reflection coefficient R_{1n}) can be calculated from boundary conditions that both the electron wave function $\psi(x, t)$ and its first derivative $\partial \psi(x,t)/\partial x$ are continuous at x = 0 and x = d (see Appendix B for details). The normalized transmitted current density is defined as the ratio of the transmitted probability current density over the incident probability current density, $w(\varepsilon, x, t) = J_t(\varepsilon, x, t)/J_i(\varepsilon, x, t)$, where the density $I(x,t) = (i\hbar/2m_{e})(\psi\nabla\psi^{*} - \psi^{*}\nabla\psi) = (i\hbar/2m_{e})(\psi\nabla\psi^{*} - \psi^{*}\nabla\psi)$ probability current $2m_e)\sum_{n=-\infty}^{\infty}\sum_{l=-\infty}^{\infty}(\psi_n\nabla\psi_l^*-\psi_n^*\nabla\psi_l)$ where $\psi_n(\psi_l)$ is the electron wavefunction with eigenenergy of $\varepsilon + n\hbar\omega$ ($\varepsilon + l\hbar\omega$), which is given by the term inside the sum sign in Eq. 3 (in the left metal), Eq. 4 (inside the gap) or Eq. 5 (in the right metal). Thus, the normalized instantaneous transmitted current density in the right-side metal (x > d), in nondimensional quantities [10,12,54,57], $\bar{\varepsilon} = \varepsilon/W$, $\bar{\omega} = \omega\hbar/W$, $\bar{t} = tW/\hbar$, $\bar{E}_F = E_F/W$, $\bar{x} = x/\lambda_0$, $\bar{d} = d/\lambda_0$, $\lambda_0 = \sqrt{\hbar^2/2m_eW}, \, \bar{V} = eV/W, \, \bar{F}_1 = eF_1\lambda_0/W, \, \bar{U}_p = U_p/W, \, \text{and} \, \bar{E}_n = \bar{\varepsilon} + n\bar{\omega} - \bar{E}_F - \bar{U}_p - 1,$ is found to be,

$$w(\bar{\varepsilon},\bar{t}) = \frac{1}{\sqrt{\bar{\varepsilon}}} \sum_{n=-\infty}^{\infty} \sum_{l=-\infty}^{\infty} \operatorname{Re}\left\{ e^{i(l-n)\bar{\omega}\bar{t}} T_{3n} T_{3l}^* D \right\},$$
(6)

where $D = e^{i \left[\sqrt{\overline{\varepsilon} + n\overline{\omega} + \overline{V}} - (\sqrt{\overline{\varepsilon} + l\overline{\omega} + \overline{V}})^*\right]\overline{x}} \left(\sqrt{\overline{\varepsilon} + l\overline{\omega} + \overline{V}}\right)^*$. The time-averaged transmitted current density is obtained as,

$$\langle w(\bar{\varepsilon}) \rangle = \sum_{n=-\infty}^{\infty} \langle w_n(\bar{\varepsilon}) \rangle, \quad \langle w_n(\bar{\varepsilon}) \rangle = \operatorname{Re}\left(|T_{3n}|^2 \sqrt{1 + n\bar{\omega}/\bar{\varepsilon} + \bar{V}/\bar{\varepsilon}} \right), \tag{7}$$

where $\langle w_n \rangle$ represents the time-averaged transmitted current density through *n*-photon process, with transmitted electrons of energy $\varepsilon + n\hbar\omega$.

For photoemission from right-side metal-vacuum interface of the gap in Fig. 1(a), electrons in the right metal would see a potential barrier subjected to a negative dc electric field $F_0 = -V/d$ (<0) and laser field $F_1 \cos(\omega t)$, as shown in Fig. 1(c). Thus, the time-dependent potential

barrier in the right metal of Fig. 1(a) (x < 0 in Fig. 1(c)), vacuum gap (0 < x < d) and left metal of Fig. 1(a) ($x \ge d$ in Fig. 1(c)) is [10,12,54,57–59],

$$\Phi(x,t) = \begin{cases} 0 & x < 0\\ E_F + W + eVx/d - eF_1xcos(\omega t) & 0 \le x < d\\ eV - eF_1dcos(\omega t) & x \ge d, \end{cases}$$
(8)

where E_F and W are the Fermi energy and work function of the right metal in Fig. 1(a) respectively, and V is the magnitude of the applied dc bias. Other parameters have the same definition as that in Eq. (1), with F_1 of opposite sign (i.e., 180 degrees out of phase) of that in Fig. 1(b) at any time instant for a given laser field.

Solving the TDSE in Eq. (2) with the potential energy given in Eq. (8) yields the electron wave function for x < 0,

$$\psi_4(x,t) = \exp\left(-\frac{i\varepsilon t}{\hbar} + ik_0 x\right) + \sum_{n=-\infty}^{\infty} R_{2n} \exp\left(-i\frac{\varepsilon + n\hbar\omega}{\hbar}t - ik_n x\right), x < 0$$
(9)

where the wavenumber $k_0 = \sqrt{2m_e\varepsilon/\hbar^2}$ and $k_n = \sqrt{2m_e(\varepsilon + n\hbar\omega)/\hbar^2}$, and R_{2n} is the reflection coefficient.

For $0 \le x < d$ in the gap, the exact solution to Eq. (2) is (see Appendix A for the method),

$$\psi_{5}(x,t) = \sum_{n=-\infty}^{\infty} \exp\left[-i\frac{\varepsilon + n\hbar\omega}{\hbar}t\right] \exp\left[\frac{ie^{2}VF_{1}\sin(\omega t)}{\hbar dm_{e}\omega^{3}} + \frac{ixeF_{1}\sin(\omega t)}{\hbar\omega} + \frac{ie^{2}F_{1}^{2}\sin(2\omega t)}{8m_{e}\hbar\omega^{3}}\right] \times [T_{4n}Ai(\eta_{n}) + T_{5n}Bi(\eta_{n})]; \qquad 0 \le x < d \quad (10)$$

representing the superposition of a set of transmitted and reflected electron waves inside the gap, where $\eta_n = \left[-\frac{E_n}{eV}d + x + \frac{eF_1\cos(\omega t)}{m_e\omega^2}\right] \left(\frac{2em_eV}{\hbar^2 d}\right)^{\frac{1}{3}}$, $E_n = \varepsilon + n\hbar\omega - E_F - W - U_p$, $U_p = e^2F_1^2/4m_e\omega^2$, and T_{4n} and T_{5n} are the coefficients.

For $x \ge d$, an exact solution of transmitted electron wave function is found to be,

$$\psi_6(x,t) = \sum_{n=-\infty}^{\infty} T_{6n} \exp\left(-i\frac{\varepsilon + n\hbar\omega}{\hbar}t\right) \exp\left[ik_n x + i\frac{eF_1 d\sin(\omega t)}{\hbar\omega}\right], x \ge d$$
(11)

where the wavenumber $k_n = \sqrt{2m_e(\varepsilon + n\hbar\omega - eV)/\hbar^2}$ due to *n*-photon contribution, and T_{6n} is the transmission coefficient.

Similarly, the coefficients T_{4n} , T_{5n} , and T_{6n} (and therefore R_{2n}) can be obtained from boundary conditions for continuous electron functions at x = 0 and x = d (see Appendix B for details). The

normalized instantaneous transmitted current density in the left-side metal of Fig. 1(a), defined as the ratio of the transmitted probability current density over the incident probability current density, $w(\varepsilon, x, t) = J_t(\varepsilon, x, t)/J_i(\varepsilon, x, t)$, is obtained as

$$w(\bar{\varepsilon},\bar{t}) = \frac{1}{\sqrt{\bar{\varepsilon}}} \sum_{n=-\infty}^{\infty} \sum_{l=-\infty}^{\infty} Re\{e^{i(l-n)\bar{\omega}\bar{t}}T_{6n}T_{6l}^*D\},\tag{12}$$

where $D = e^{i \left[\sqrt{\overline{\varepsilon} + n\overline{\omega} - \overline{V}} - (\sqrt{\overline{\varepsilon} + l\overline{\omega} - \overline{V}})^*\right]\overline{x}} \left(\sqrt{\overline{\varepsilon} + l\overline{\omega} - \overline{V}}\right)^*$. The time-averaged transmitted current density is found to be,

$$\langle w(\bar{\varepsilon}) \rangle = \sum_{n=-\infty}^{\infty} \langle w_n(\bar{\varepsilon}) \rangle, \quad \langle w_n(\bar{\varepsilon}) \rangle = \operatorname{Re}\left(|T_{6n}|^2 \sqrt{1 + n\bar{\omega}/\bar{\varepsilon} - \bar{V}/\bar{\varepsilon}} \right), \tag{13}$$

III. RESULTS AND DISCUSSION

In our calculation, positive dc field ($F_0 > 0$) and negative dc field ($F_0 < 0$) denote the electron emission from left and right metal surfaces of the nano-vacuum gap with the external dc voltage $V (=|F_0|d)$, respectively (cf. Fig. 1). Unless mentioned otherwise, the default value of the laser wavelength is 800 nm ($\hbar \omega = 1.55 \text{ eV}$), the metals on both sides of the gap are assumed to be gold [30,32–35,54], with Fermi energy $E_F = 5.53 \text{ eV}$ and work function W = 5.1 eV, and the photoemission current is calculated from Eqs. (7) and (13). Since most of the electrons are emitted with initial energies near the Fermi level [10,50,55,60], for simplicity we choose the electron initial energy $\varepsilon = E_F$ for the following calculations.

In Fig. 2, we plot the photoelectron energy spectra under different dc fields with fixed gap distance d = 5 nm. The results for dc field $F_0 = 0$ are calculated from our recent work [54]. As shown in Fig. 2(a), adding a strong dc field $F_0 = 1$ V/nm increases the left-to-right photoelectron emission current by about three orders of magnitude compared to the no dc bias case $F_0 = 0$. It also shifts the dominant electron emission process from four-photon over-barrier emission (n = 4, cf. the ratio of the metal work function over single photon energy $W/\hbar\omega \approx 3.29$) to dc-assisted optical tunneling emission (n < 4). Further increasing the dc field F_0 from 1 to 3 V/nm brings the dominant emission to less photon absorption (from n = 3 to 2). This can be explained by that the potential barrier near the left metal-vacuum interface of nanogap becomes narrower with the increase of F_0 , enabling transition processes with less photons (cf. Fig. 2(b)).

However, as a larger dc field leads to a higher potential barrier at the right vacuum-metal interface of the gap, electrons in the right metal need absorb more photons to overcome the potential barrier for emission (cf. Fig. 2(d)). This leads to a dramatic decrease of right-to-left photoemission current and a shift of the dominant emission to much higher order multiphoton absorption, as shown in Fig. 2(c).

These observed trends are also reflected in Fig. 3, which shows the total time-averaged transmission current density $\langle w \rangle$ from left- (Fig. 3(a)) and right-side (Fig. 3(b)) surfaces of nanogap as a function of laser field F_1 with different applied dc bias. The increasing (decreasing) slope of the curve of $\langle w \rangle$ with dc field F_0 manifests the shift of main emission process to the higher (lower) order multiphoton absorption. Here, the slope of $\langle w \rangle$ versus F_1 follows the power-law scaling of photoemission $\langle w \rangle \propto F_1^{2n}$, indicating the dominant *n*-photon emission process. The value of *n* labeled in Fig. 3(a) and 3(b) is consistent with the observation in Figs. 2(a) and 2(c) (i.e. the cases with $F_0 = \pm 1$ and ± 3 V/nm)).

Figures 3(c) and 3(d) show the total time-averaged emission current density $\langle w \rangle$ as a function of laser field F_1 for different gap distances d when the external dc field is fixed at 3 V/nm. For the photocurrent emitted from left surface (Fig. 3(c)), the slope of $\langle w \rangle$ is insensitive to the gap spacing d and it follows the scale $\langle w \rangle \propto F_1^{2n}$ with n = 1.9, indicating the dominant two-photon absorption. The insensitivity of slope to d is due to the almost unchanged potential barrier near the left metalvacuum surface during the increase of d in our model (cf. Fig. 3(e)). It is noteworthy that, in response to changing conditions related to wave function penetration into the barrier, in particular, the location of the barrier onset and its effective work function due to image and space charges [29,55,56,61], the potential barrier does in fact change with the gap distance d, which requires more careful further investigation. For the emission from right metal surface, as dincreases, electrons need to absorb more photons to transport through the gap with higher potential barrier (cf. Fig. 3(f)), thus the right-to-left emission current $\langle w \rangle$ significantly decreases and its slope increases with the increasing d, as shown in Fig. 3(d).

In Fig. 4, we plot the total emission current density $\langle w \rangle$ as a function of gap distance *d* under various dc fields F_0 and laser fields F_1 . Without the dc bias (i.e., $F_0 = 0$), the emission current $\langle w \rangle$ from either side of the vacuum gap continuously oscillates around the current from a single surface (i.e. the dashed line) as *d* increases. This oscillation behavior is due to the interference of electron plane waves inside the gap due to the reflections from the metal-vacuum interface, and the

oscillatory behavior occurs in the multiphoton over-barrier dominant emission regime, which has been demonstrated previously [54]. After applying a large dc field (e.g. $F_0 = \pm 4$ V/nm), it is found that the oscillation in the current is greatly reduced with gap spacing *d*. This is because of the shift of main emission away from multiphoton over-barrier regime under a strong dc bias (cf. Figs. 2(a) and 2(c)), sufficiently weakening the interference effect of electron waves inside the gap.

Besides, our calculation shows with a very narrow gap (d < 0.5 nm), the emission current from the left and right surfaces has the same order of magnitude, regardless of applied laser intensity or dc bias, since direct tunneling dominates the electron transmission [54]. As the gap distance dincreases, compared to the emission current from left metal surface, the current from right surface is more greatly suppressed, as shown in Fig. 4, resulting in the rectified response of photoelectron emission. This indicates that varying the gap distance could provide very different degree of rectification to the photoemission in a dc-biased vacuum gap. Our results show the gap distance of larger than 1 nm is adequate to achieve almost full rectification for dc field $F_0 \ge 1$ V/nm and laser field $F_1 \le 8$ V/nm, and the rectification effect is more pronounced with stronger external dc bias. It is important to point out that, in practice, the externally applied field is expected to be substantially smaller than the values of the local fields noted here, because of typically strong field enhancement [27] and possible plasmonic resonant enhancement [15] near nanotips forming the gap. This may suggest a practical way to suppress the impact of electron signal from the direction opposite to dc field in the two-metal-tip one-way photodetection, by choosing an optimal gap spacing under a given dc bias.

In Figs. 5(a) and 5(b), we plot the total time-averaged transmission current density $\langle w \rangle$ as a function of dc field F_0 under different laser fields F_1 . In Fig. 5(c), we display the net emission current density $\langle w \rangle_{net}$, defined as the difference between the left-to-right and the right-to-left emission current, as a function of external dc bias V for laser field $F_1 = 0.4$, 0.8 and 1 V/nm. For zero dc bias voltage, by symmetry, emission current density from left and right metal surfaces are equal, thus no net photocurrent $\langle w \rangle_{net}$ is generated. Due to the nonlinear emission process with respect to dc field F_0 shown in Figs. 5(a) and 5(b), the photoemission from right surface of gap is gradually suppressed with the increasing dc bias while that from the left increases, which leads to the rectification response caused by applied dc bias to the photoemission (Fig. 5 (c)). The calculated increasing trend in Fig. 5(c) is in good agreement with the experimental measurement

of photocurrent versus applied dc voltage in the periodic metal-vacuum nanotip array (cf. Fig.4 in Ref. [34]).

The spatiotemporal evolution of electron density $|\psi(x,t)|^2$ emitted from left and right metal surfaces under different combinations of dc and laser electric fields is displayed in Figs. 6 and 7, respectively. Here, the gap distance d is fixed at 5 nm. As seen in Fig. 6(a), with a larger applied dc field $F_0 = 1$ V/nm and weaker laser field $F_1 = 0.1$ V/nm, parts of electrons emitted from left metal surface are reflected back and forth inside the gap (0 < x < 5 nm). These emission patterns are in line with the numerical simulation results in Fig. 2(a) of Ref. [38]. Increasing the laser field F_1 in Figs. 6(a)-6(c) is found to produce stronger oscillatory features within the gap. It is due to the stronger backpropagation and acceleration processes (i.e., quiver motion) of emitted electrons under strong laser electric fields [16]. When adding a stronger dc field $F_0 = 5$ V/nm, dc field-like electron emission pattern dominates the whole regime, as shown in Figs. 6(d)-6(f). Due to the strong acceleration, electrons enter the right-side metal with higher velocity compared to the case with $F_0 = 1$ V/nm (cf. the slope of white solid lines representing classical emission trajectories). On the other hand, for the emission from right surface, as seen in Fig. 7, the addition of 1 V/nm dc field confines most of electrons inside the vacuum gap, and only when the laser field F_1 is increased up to 8 V/nm could a small part of electrons escape from gap into left metal (Fig. 7(c)). Similar trend can be observed in Figs. 7(d)-7(f) when applying a larger dc field of 5 V/nm, where most of the electrons are constrained in the surface strong current oscillation regime.

IV. CONCLUSION

In summary, by exactly solving the time-dependent Schrödinger equation, we present an analytical model for nonlinear photoelectron emission from a dc-biased nanoscale metal-vacuummetal gap driven by a laser field. Our results reveal the underlying photoemission processes, timeaveraged emission current and spatiotemporal dynamics of photoelectrons from left- and rightside surfaces of the nanogap under different combinations of dc bias, laser fields and gap distances. Our calculation shows that applying a strong dc bias can greatly reduce the interference oscillation in the single-sided transmission current, due to the shift of dominant emission away from multiphoton over-barrier regime. Our results demonstrate that in addition to the dc bias, varying the gap spacing can greatly influence the rectification to the photoelectron emission in a dc-biased vacuum gap. This may provide guidance to suppress the impact of electron signal from the direction opposite to dc field on the one-way photodetection by choosing proper gap spacing with a given dc bias. Our work would be helpful for understanding the photoemission properties in dcbiased asymmetric metal-vacuum nanojunctions, and for the design of advanced quantum plasmonic nanoantennas and ultrafast photodetectors. Future work will consider the effects of ultrashort pulsed laser illumination [16], laser penetration depth, laser heating [62], space charge [29,55,56], oscillatory Schottky barrier lowering [29,55,56,61], surface dielectric coating [15,63,64], roughness and defects, asymmetric geometry [27], and dissimilar electrode materials [56] on photoemission in a nanogap.

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APPENDIX A: EXACT SOLUTION OF ELECTRON WAVE FUNCTION

Following Truscott [10,65], the time-dependent potential energy for $0 \le x < d$ can be written as $\Phi(x,t) = V(x,t) - xf(t)$. Thus, the TDSE (Eq.(2)) can be transformed to the coordinate system ξ , t, where $\xi = x - q(t)$, the displacement $q(t) = (1/m_e) \int^t p(t')dt'$, and $p(t) = \int^t f(t')dt'$, by assuming that $\psi(x,t) = \phi(\xi,t)\chi(x,t)$, with $\chi(x,t) = \exp[-iEt/\hbar + ixp(t)/\hbar - (i/2\hbar m) \int^t p^2(t')dt']$, and E being a constant. Then, we have,

$$i\hbar \frac{\partial \phi(\xi,t)}{\partial t} = \left[-\frac{\hbar^2}{2m_e} \frac{\partial^2}{\partial \xi^2} + U(\xi,t) - E \right] \phi(\xi,t), \tag{A1}$$

with $U(\xi, t) = V(x, t)$. By separation of variables, $\phi(\xi, t)$ in Eq. (A1) can be solved. From $\psi(x, t) = \phi(\xi)\chi(x, t)$, we obtain exact solution of electron wave function.

For the photoelectron emission from left metal-vacuum interface of the gap in Fig.1(a), we have the potential energy $\Phi(x, t) = V(x) - xf(t)$, with $V(x, t) = V_0 - eVx/d$ where $V_0 = E_F + W$ and $f(t) = eF_1 \cos(\omega t)$ (cf. Eq. 1), and

$$\phi(\xi, t) = g(\xi) \exp\left[\frac{e^2 V F_1 \sin(\omega t)}{i\hbar d m_e \omega^3}\right]$$
(A2)

where $g(\xi) = Ai(-\eta) \pm iBi(-\eta)$ is the solution of the equation $-(\hbar^2/2m_e)\partial^2 g(\xi)/\partial\xi^2 + (V_0 - E - eV\xi/d)g(\xi) = 0$, where $\eta = (2em_eV/d\hbar^2)^{1/3}[(E - V_0)d/eV + \xi]$ [81][86]. Here, "-" in $g(\xi)$ denotes the electron wave travelling towards +*x* direction; "+" denotes the electron wave travelling towards -*x* direction. Due to the reflection of electron waves at metal-vacuum surfaces of *x*=0 and *d* (cf. Fig. 1(b)), the electron wave function $\psi(x, t)$ inside the vacuum gap $(0 \le x < d)$ should be the superposition of wave functions towards +*x* direction and -*x* direction. Then, from $\psi(x, t) = \phi(\xi)\chi(x, t)$, we obtain Eq. (4) with $E = \varepsilon + n\hbar\omega - e^2F_1^2/4m_e\omega^2$.

For the photoelectron emission from right vacuum-metal interface of the gap in Fig. 1(a), we have the potential energy $\Phi(x,t) = V(x) - xf(t)$, with $V(x,t) = V_0 + eVx/d$ where $V_0 = E_F + W$ and $f(t) = eF_1 \cos(\omega t)$ (cf. Eq. 8), and

$$\phi(\xi, t) = g(\xi) \exp\left[-\frac{e^2 V F_1 \sin(\omega t)}{i \hbar d m_e \omega^3}\right]$$
(A3)

where $g(\xi) = Ai(\eta) \pm iBi(\eta)$ is the solution of the equation $-(\hbar^2/2m_e)\partial^2 g(\xi)/\partial\xi^2 + (V_0 - E + eV\xi/d)g(\xi) = 0$, where $\eta = (2em_eV/d\hbar^2)^{1/3}[\xi - (E - V_0)d/eV][81][86]$. Here, "+" in $g(\xi)$ denotes the electron wave travelling towards +x direction; "-" denotes the electron wave travelling towards -x direction. Due to the reflection of electron waves at metal-vacuum surfaces of x=0 and d (cf. Fig. 1(c)), the electron wave function $\psi(x, t)$ inside the vacuum gap $(0 \le x < d)$ should be the superposition of wave functions towards +x direction and -x direction. Then, from $\psi(x, t) = \phi(\xi)\chi(x, t)$, we obtain Eq. (10) with $E = \varepsilon + n\hbar\omega - e^2F_1^2/4m_e\omega^2$.

APPENDIX B: CALCULATION OF TRANSMISSION AND REFLECTION COEFFICIENTS

For the photoemission from left metal-vacuum interface of the gap in Fig.1(a), by applying the boundary conditions that both the electron wave function $\psi(x, t)$ and its derivative $\partial \psi(x, t)/\partial x$ are continuous at x = 0 and x = d (cf. Fig. 1(b)), and taking Fourier transform, we obtain, in nondimensional quantities, $\bar{\varepsilon} = \varepsilon/W$, $\bar{\omega} = \omega\hbar/W$, $\bar{t} = tW/\hbar$, $\bar{E}_F = E_F/W$, $\bar{x} = x/\lambda_0$, $\bar{d} = d/\lambda_0$, $\lambda_0 = \sqrt{\hbar^2/2m_eW}$, $\bar{V} = Ve/W$, $\bar{F}_1 = F_1e\lambda_0/W$, $\bar{U}_p = U_p/W$, the following equations,

$$\sum_{n=-\infty}^{\infty} T_{1n} \left[\sqrt{\overline{\varepsilon} + m\overline{\omega}} P_{1n(n-m)} + Q_{1n(n-m)} \right] + T_{2n} \left[\sqrt{\overline{\varepsilon} + m\overline{\omega}} P_{2n(n-m)} + Q_{2n(n-m)} \right]$$

$$= 2\sqrt{\overline{\varepsilon}} \delta(m)$$
(A4)

$$\sum_{n=-\infty}^{\infty} \left[\sqrt{\bar{\varepsilon} + m\bar{\omega} + \bar{V}} U_{1n(n-m)} - V_{1n(n-m)} \right] T_{1n} + \left[\sqrt{\bar{\varepsilon} + m\bar{\omega} + \bar{V}} U_{2n(n-m)} - V_{2n(n-m)} \right] T_{2n}$$

$$= 0$$
(A5)

$$\sum_{n=-\infty}^{\infty} T_{1n} U_{1n(n-m)} + T_{2n} U_{2n(n-m)} = T_{3m} \exp\left(i\bar{d}\sqrt{\bar{\varepsilon} + m\bar{\omega} + \bar{V}}\right)$$
(A6)

where $\delta(m)$, $P_{1n(n-m)}$, $Q_{1n(n-m)}$, $P_{2n(n-m)}$, $Q_{2n(n-m)}$, $U_{1n(n-m)}$, $V_{1n(n-l)}$, $U_{2n(n-m)}$, and $V_{2n(n-l)}$ are given by,

$$\delta(m) = \begin{cases} 1, & m = 0, \\ 0, & m \neq 0, \end{cases}$$
 (A7a)

$$P_{1nl} = \frac{1}{2\pi} \int_0^{2\pi} p_{1n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad Q_{1nl} = \frac{1}{2\pi} \int_0^{2\pi} q_{1n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad (A7b)$$

$$P_{2nl} = \frac{1}{2\pi} \int_0^{2\pi} p_{2n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad Q_{2nl} = \frac{1}{2\pi} \int_0^{2\pi} q_{2n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad (A7c)$$

$$p_{1n}(\overline{\omega}\overline{t}) = Ai(\alpha_n)f(\overline{\omega}\overline{t}),\tag{A7d}$$

$$q_{1n}(\overline{\omega}\overline{t}) = [Ai(\alpha_n)\frac{\overline{F}_1\sin(\overline{\omega}\overline{t})}{\overline{\omega}} + iAi'(\alpha_n)(\overline{V}/\overline{d})^{\frac{1}{3}}]f(\overline{\omega}\overline{t}), \tag{A7e}$$

$$p_{2n}(\overline{\omega}\overline{t}) = Bi(\alpha_n)f(\overline{\omega}\overline{t}), \tag{A7}f)$$

$$q_{2n}(\overline{\omega}\overline{t}) = [Bi(\alpha_n)\frac{\overline{F}_1\sin(\overline{\omega}\overline{t})}{\overline{\omega}} + iBi'(\alpha_n)(\overline{V}/\overline{d})^{\frac{1}{3}}]f(\overline{\omega}\overline{t}), \tag{A7}g)$$

$$U_{1nl} = \frac{1}{2\pi} \int_0^{2\pi} u_{1n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad V_{1nl} = \frac{1}{2\pi} \int_0^{2\pi} v_{1n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad (A7h)$$

$$U_{2nl} = \frac{1}{2\pi} \int_0^{2\pi} u_{2n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad V_{2nl} = \frac{1}{2\pi} \int_0^{2\pi} v_{2n}(\overline{\omega}\overline{t}) e^{-il\overline{\omega}\overline{t}} d(\overline{\omega}\overline{t}), \quad (A7i)$$

$$u_{1n}(\overline{\omega}\overline{t}) = Ai(\gamma_n)f(\overline{\omega}\overline{t}), \tag{A7j}$$

$$v_{1n}(\overline{\omega}\overline{t}) = [Ai(\gamma_n)\frac{\overline{F}_1\sin(\overline{\omega}\overline{t})}{\overline{\omega}} + iAi'(\gamma_n)(\overline{V}/\overline{d})^{\frac{1}{3}}]f(\overline{\omega}\overline{t}),$$
(A7k)

$$u_{2n}(\overline{\omega}\overline{t}) = Bi(\gamma_n)f(\overline{\omega}\overline{t}), \tag{A7l}$$

$$v_{2n}(\overline{\omega}\overline{t}) = [Bi(\gamma_n)\frac{\overline{F}_1\sin(\overline{\omega}\overline{t})}{\overline{\omega}} + iBi'(\gamma_n)(\overline{V}/\overline{d})^{\frac{1}{3}}]f(\overline{\omega}\overline{t}), \tag{A7m}$$

$$f(\overline{\omega}\overline{t}) = \exp\left[-i\frac{2\overline{F}_1\overline{V}}{\overline{d}\overline{\omega}^3}\sin(\overline{\omega}\overline{t}) + i\frac{\overline{F}_1^2}{4\overline{\omega}^3}\sin(2\overline{\omega}\overline{t})\right],\tag{A7n}$$

with $\alpha_n = -[\bar{E}_n \bar{d}/\bar{V} + 2\bar{F}_1 \cos(\bar{\omega}\bar{t})/\bar{\omega}^2](\bar{V}/\bar{d})^{\frac{1}{3}}$, $\gamma_n = -[\bar{E}_n \bar{d}/\bar{V} + \bar{d} + 2\bar{F}_1 \cos(\bar{\omega}\bar{t})/\bar{\omega}^2](\bar{V}/\bar{d})^{\frac{1}{3}}$, and $\bar{E}_n = \bar{\varepsilon} + n\bar{\omega} - \bar{E}_F - \bar{U}_p - 1$. The coefficients T_{1n} , T_{2n} , and T_{3n} (and therefore R_{1n}) is then calculated from Equations (A4), (A5) and (A6).

For the photoemission from right vacuum-metal interface of the gap in Fig. 1(a), applying the boundary conditions yields the almost same equations as the case from left metal surface above, except that " \bar{V} " in Eqs. (A5), (A6) and (A7n) is replaced by " $-\bar{V}$ ", "+" in Eqs. (A7e), (A7g), (A7k) and (A7m) is replaced by "-", $\alpha_n = [2\bar{F}_1 \cos(\bar{\omega}\bar{t})/\bar{\omega}^2 - \bar{E}_n \bar{d}/\bar{V}](\bar{V}/\bar{d})^{\frac{1}{3}}$, and $\gamma_n = [\bar{d} + 2\bar{F}_1 \cos(\bar{\omega}\bar{t})/\bar{\omega}^2 - \bar{E}_n \bar{d}/\bar{V}](\bar{V}/\bar{d})^{\frac{1}{3}}$.

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Fig. 1. (a) Schematic of metal-vacuum-metal nanogap with a dc bias V under the illumination of laser field. d is the gap distance. (b) Energy diagram for photoelectron emission from left metal-vacuum interface of the gap in (a). Electrons with the initial energy ε would see a potential barrier subjected to a positive dc electric field $F_0 = V/d$ (> 0) and laser field $F_1 \cos(\omega t)$. (c) Energy diagram for photoelectron emission from right metal-vacuum interface of the gap in (a). Electrons would see a potential barrier with a negative dc electric field $F_0 = -V/d$ (< 0) and laser field $F_1 \cos(\omega t)$ with F_1 of opposite sign of that in (b) at any time instant for a given laser field.



Fig. 2. (a) Photoelectron energy spectra and (b) emission mechanisms for dc field $F_0 = 0$, 1 and 3 V/nm. (c) photoelectron energy spectra and (d) emission mechanisms for dc field $F_0 = 0$, -1 and -3 V/nm. Here, laser field F_1 is fixed at 1 V/nm and gap distance d = 5 nm.



Fig. 3. Normalized total time-averaged emission current density $\langle w \rangle$ as a function of laser field F_1 for (a), (b) various dc fields F_0 and (c), (d) various gap distances d. In (a), (b), the gap distance d is fixed at 5 nm. The dashed lines denote the scaling $\langle w \rangle \propto F_1^{2n}$. n = 2.8, 1.9, 6.5 and 12.4 when $F_0 = 1$, 3, -1, and -3 V/nm is consistent with the observed orders of domination emission channel in Figs. 2(a) and 2(c). Emission mechanisms from (e) left- and (f) right-side metal surface of the vacuum gap of Fig. 1(a) under the same laser electric field and dc bias for different gap distances $(d_2 > d_1)$.



Fig. 4. Normalized total time-averaged emission current density $\langle w \rangle$ as a function of gap distance *d* for different dc fields F_0 and laser fields F_1 . Dashed lines denote the emission current density from single surface when the right-side metal in Fig. 1(a) is removed, which is obtained from Ref. [10].



Fig. 5. (a), (b) Normalized total time-averaged emission current density $\langle w \rangle$ as a function of dc field F_0 for different laser fields F_1 . (c) Dependence of net emission current density $\langle w \rangle_{net}$, defined as the difference between the left-to-right and the right-to-left emission current, on the applied dc bias for different laser fields F_1 . Here, gap distance d is fixed at 5 nm.



Fig. 6. Time-dependent emission electron density $|\psi(x,t)|^2$ from left metal surface of the nanogap in Fig. 1(a) as a function of time *t* and space *x* under various combinations of dc and laser fields. Dotted white curves show the laser electric field for reference. Solid white lines represent the corresponding classical trajectories of emitted electrons, showing good agreement with the electron dynamics calculated from our model. The emission time of classical trajectory is set at around the beginning of laser period. Here, gap distance *d* is fixed at 5 nm. The unit of dc field F_0 and laser field F_1 is V/nm in all figures.



Fig. 7. Time-dependent emission electron density $|\psi(x, t)|^2$ from right metal surface of the nanogap in Fig. 1(a) as a function of time *t* and space *x* under various combinations of dc and laser fields. Here, gap distance *d* is fixed at 5 nm. The unit of dc field F_0 and laser field F_1 is V/nm in all figures.